

**COURSE TITLE:** INTRODUCTION TO CMOS PROCESSING

**COURSE CODE:** EE2520

**Textbook:** Integrated Circuit Fabrication (Science and  
Technology)

**Authors:** James D Plummer and Peter B. Griffith

# Introduction

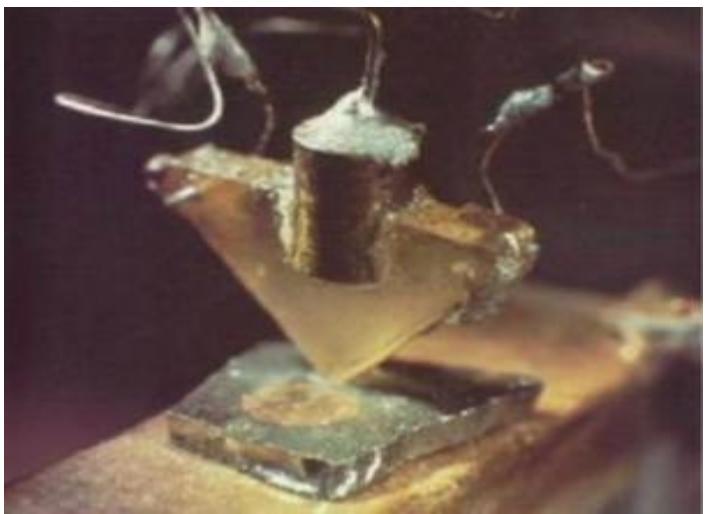
## (Lecture 1)

# KEY CONCLUSIONS

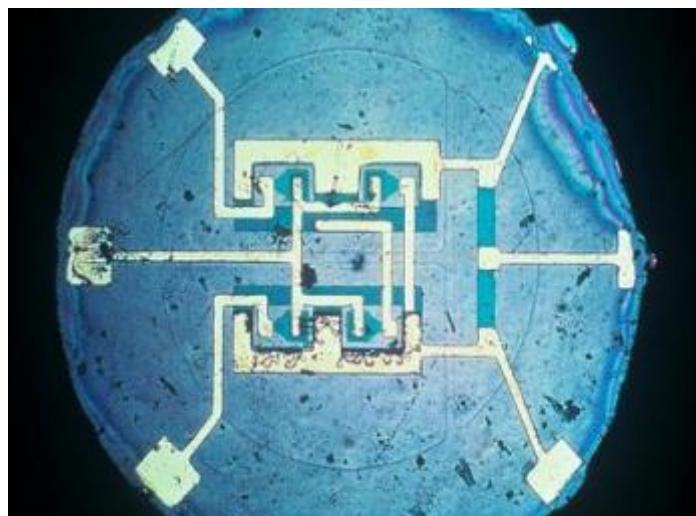
By the end of Introduction Lecture(s), you should be familiarized with

- ❖ History of Integrated Circuits
- ❖ Planar Process
- ❖ Moore's Law
- ❖ Dennard Scaling
- ❖ Technology Node
- ❖ Unit Processes
- ❖ Course Objectives

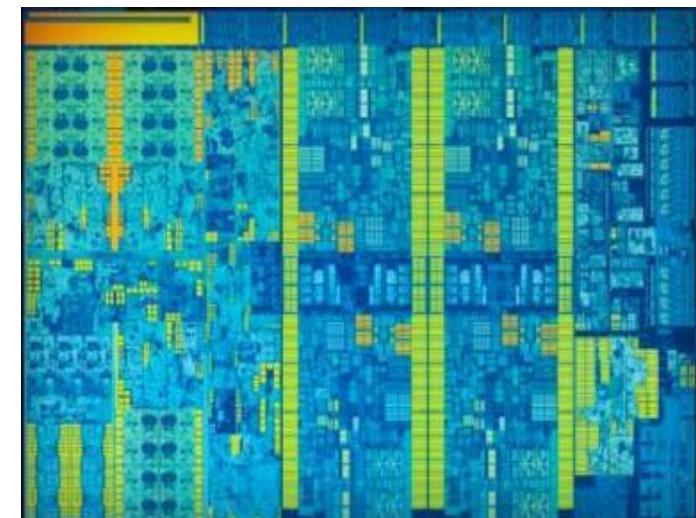
# 1948 - Present



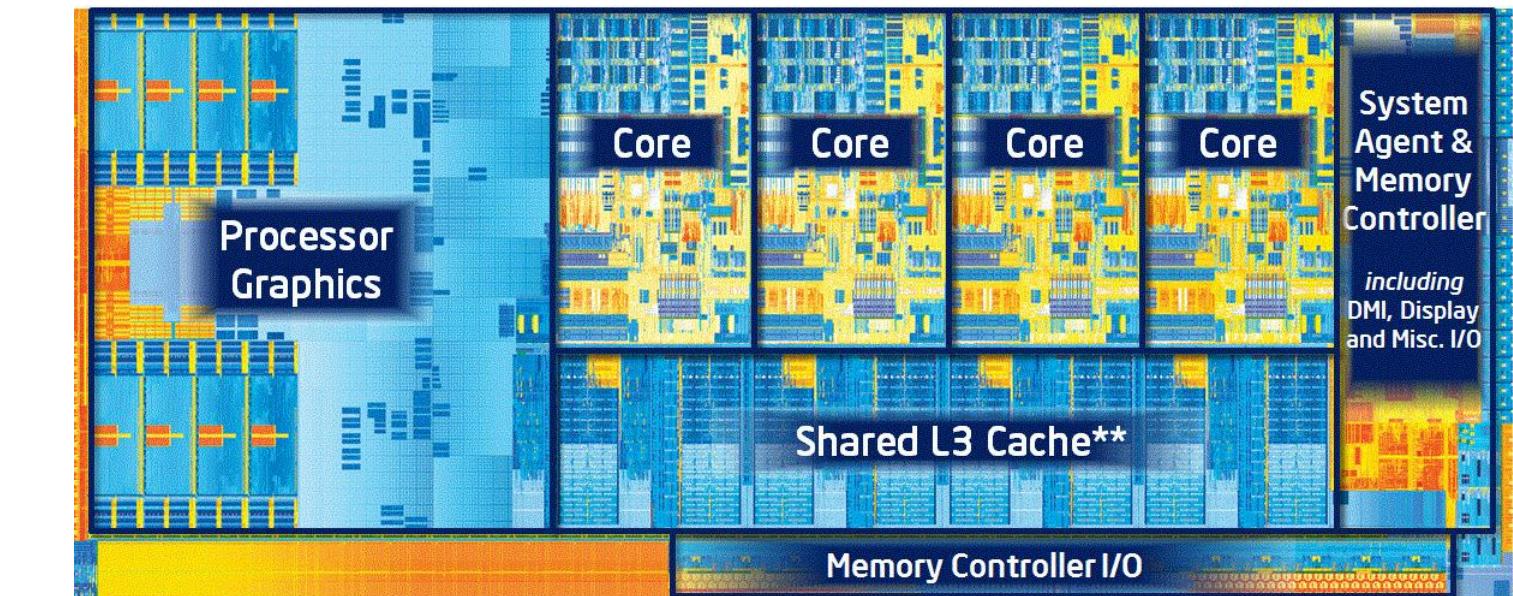
First Solid State Device



First Integrated Circuit

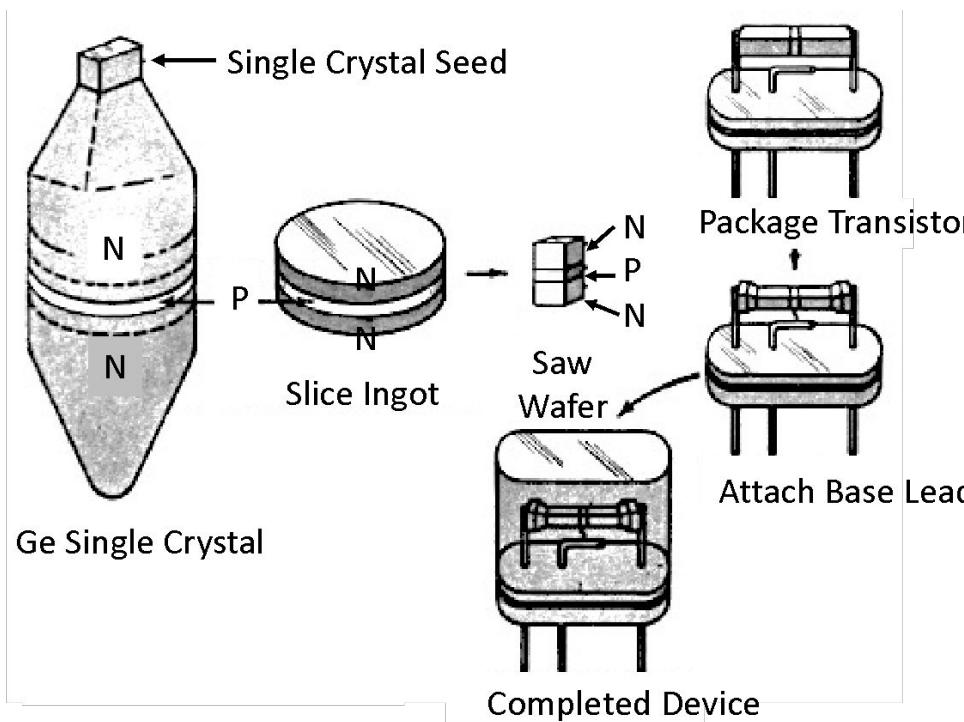


Latest Microprocessor

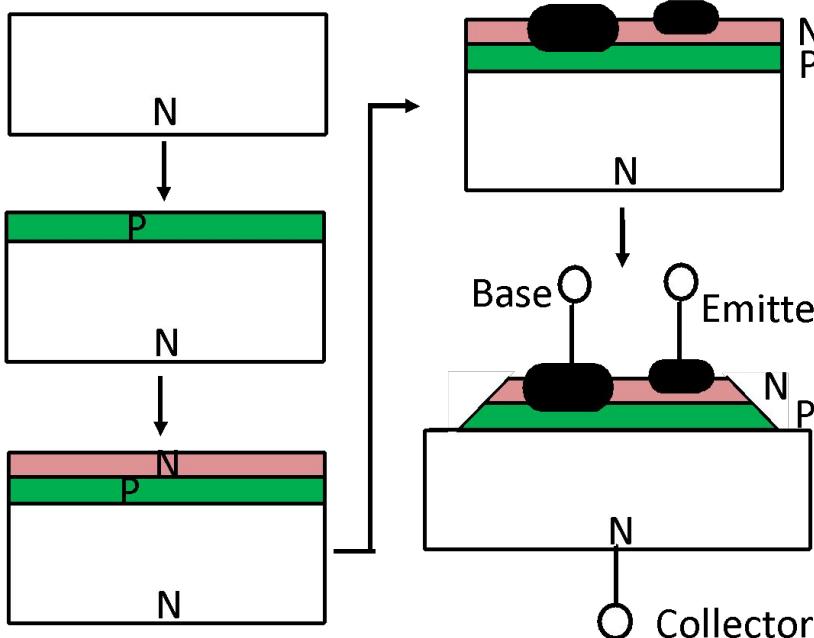


A Complex Chip (i7 processor)

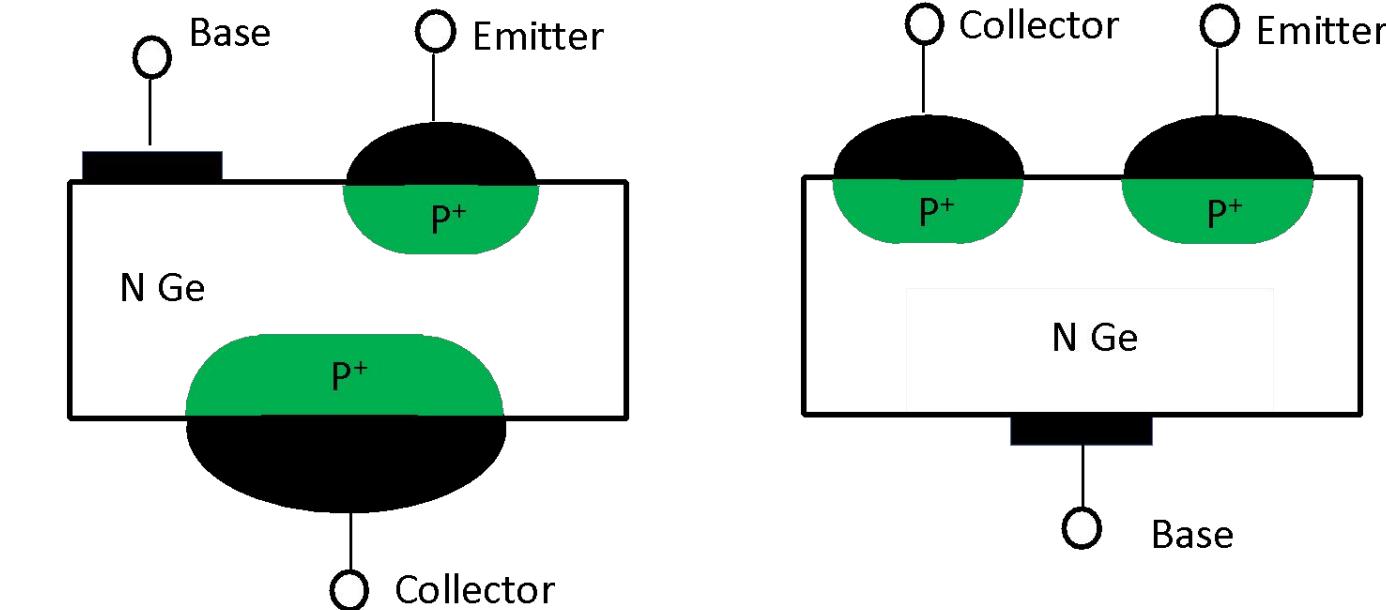
# Bulk Vs Planar



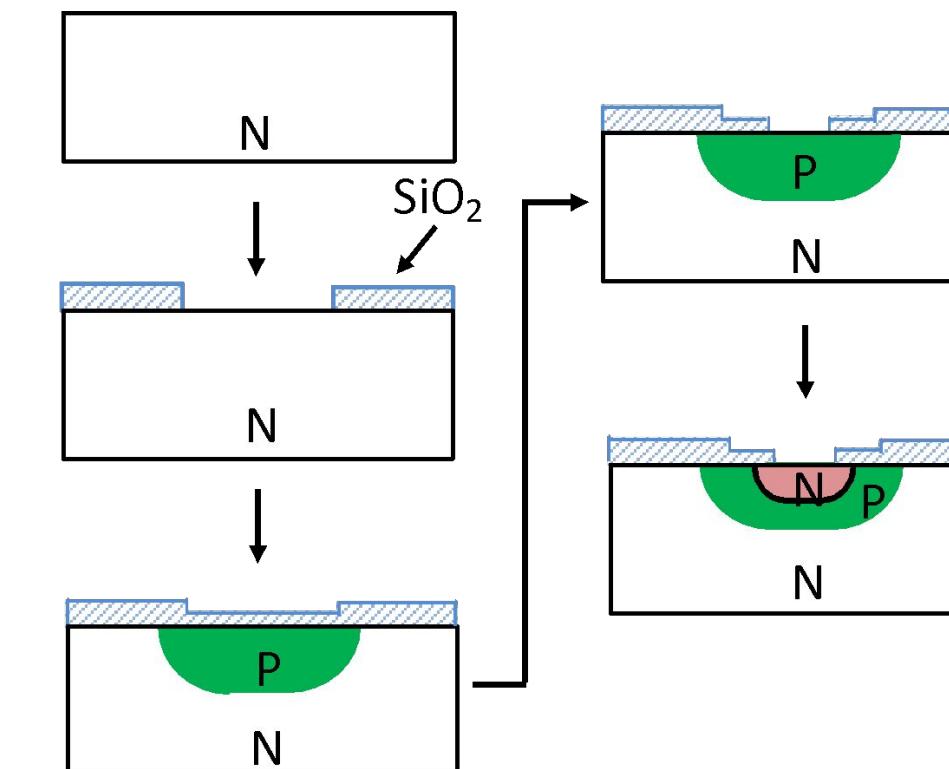
Grown junction transistor technology of the 1950s



Double diffused transistor technology of the 1950s

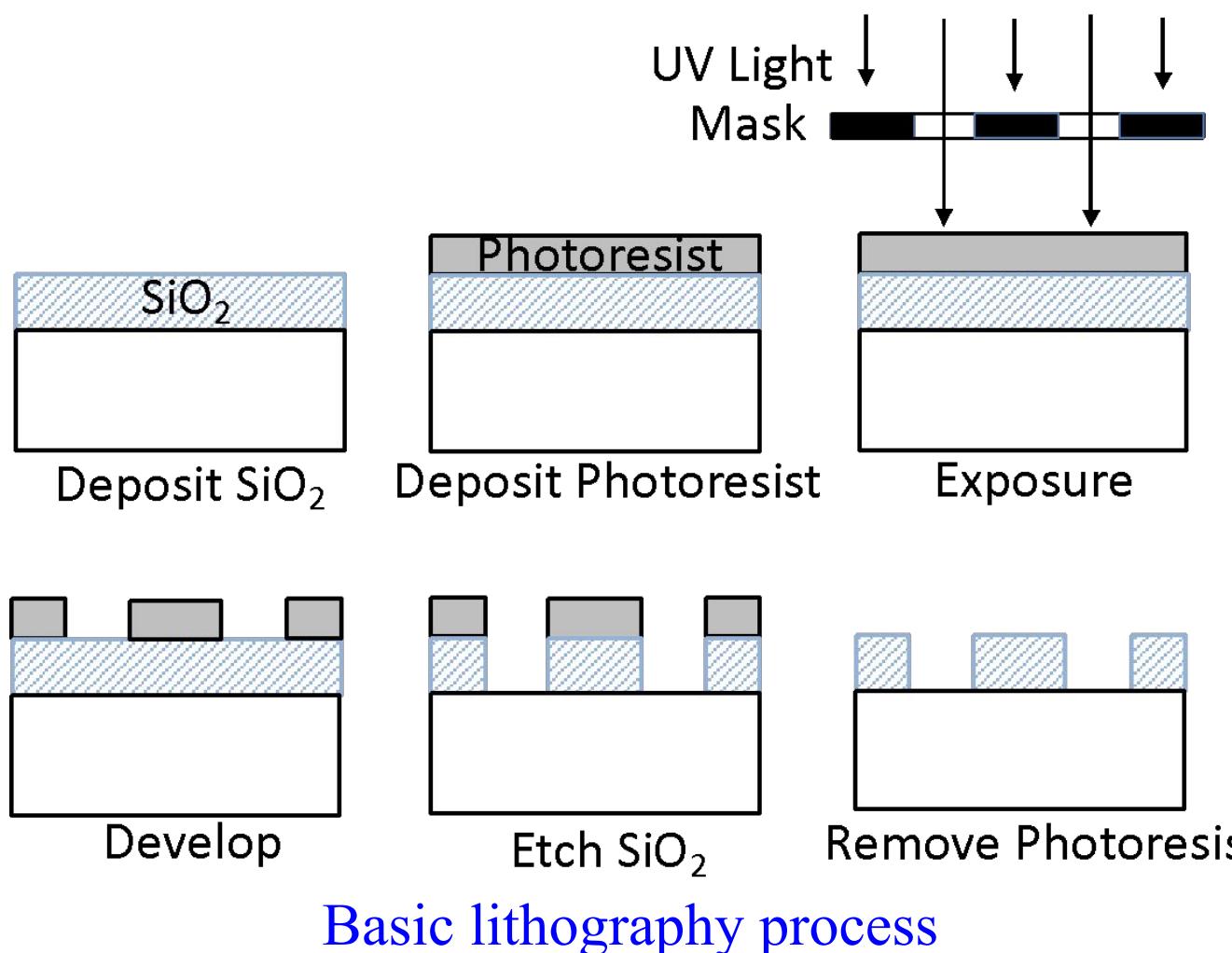


Alloy junction technology of the 1950s.

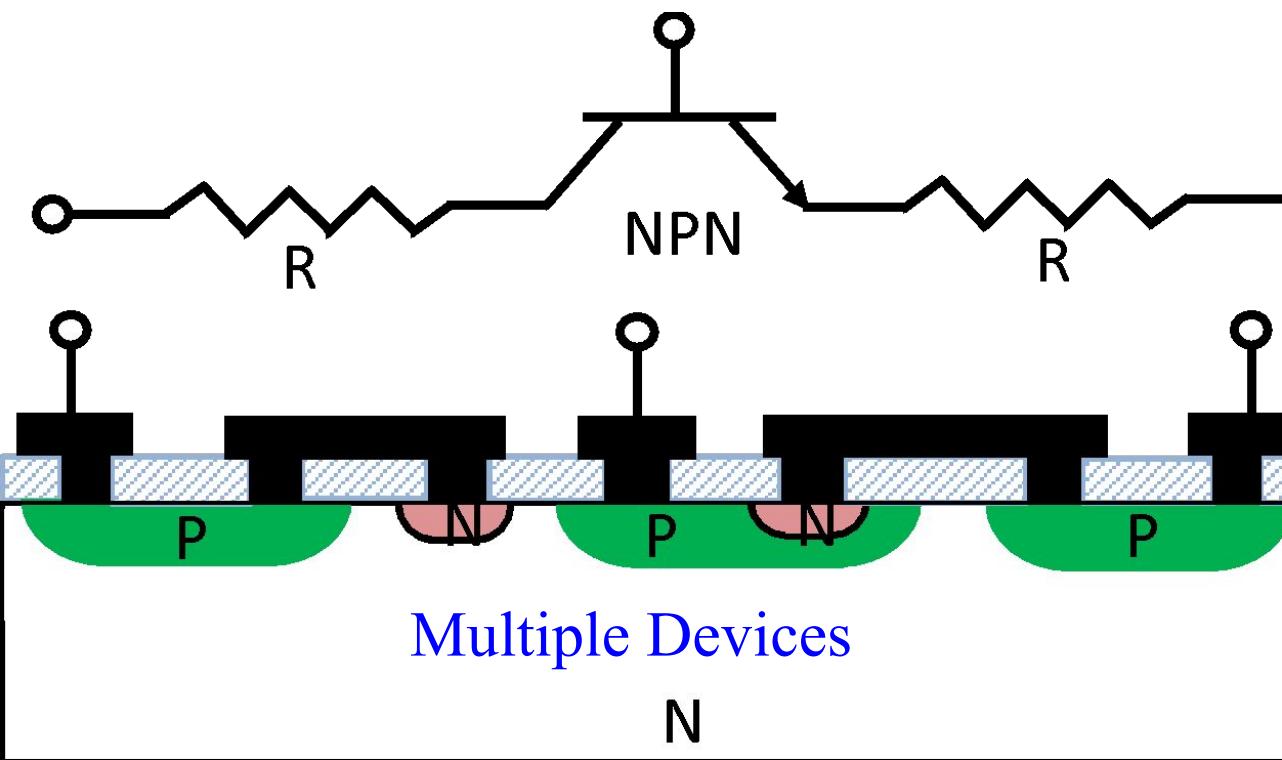


The planar process (Hoerni - Fairchild, late 1950s).

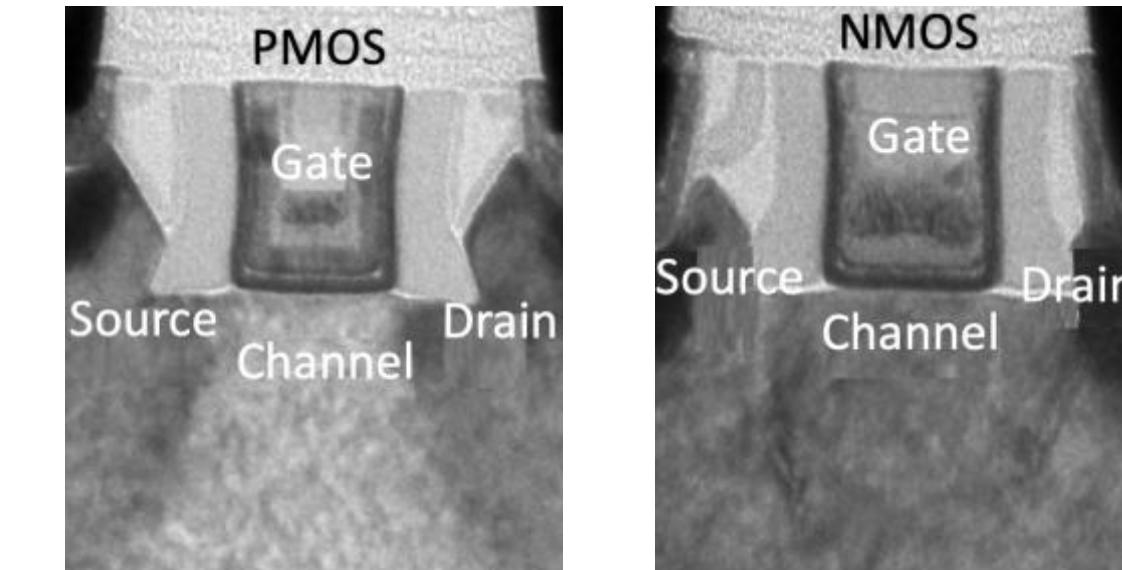
# Planar Process



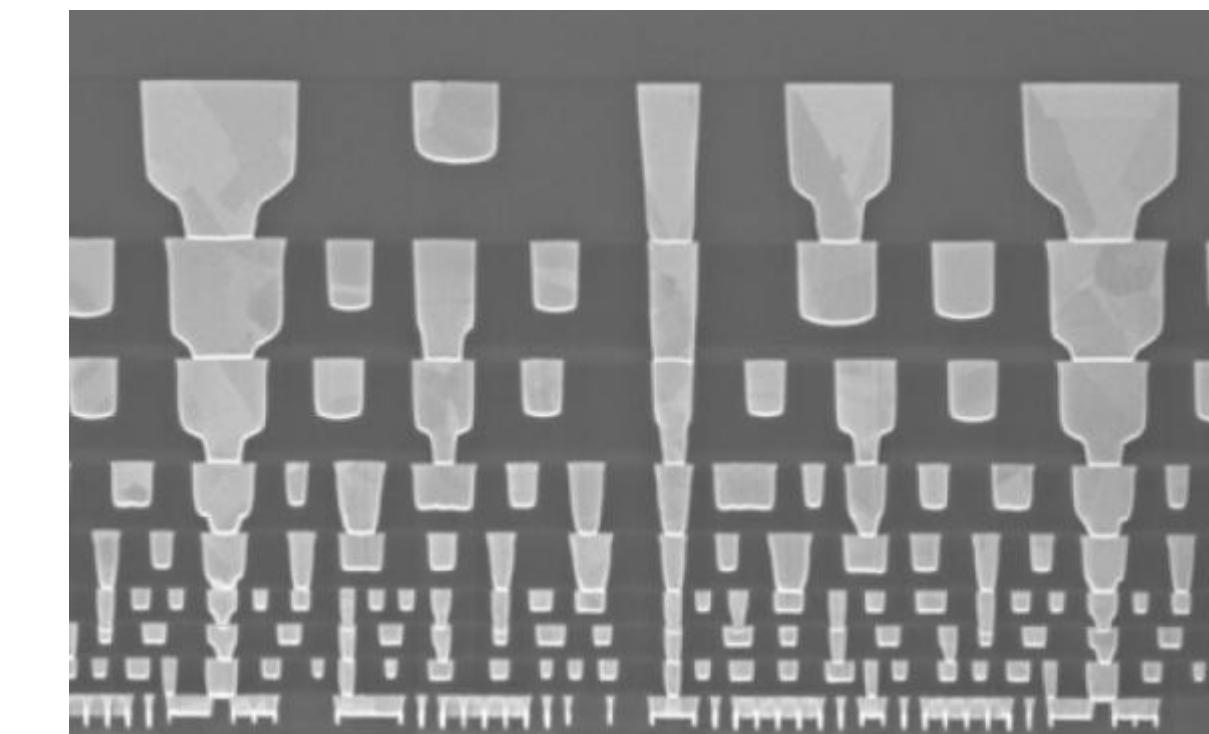
Basic lithography process



Multiple Devices

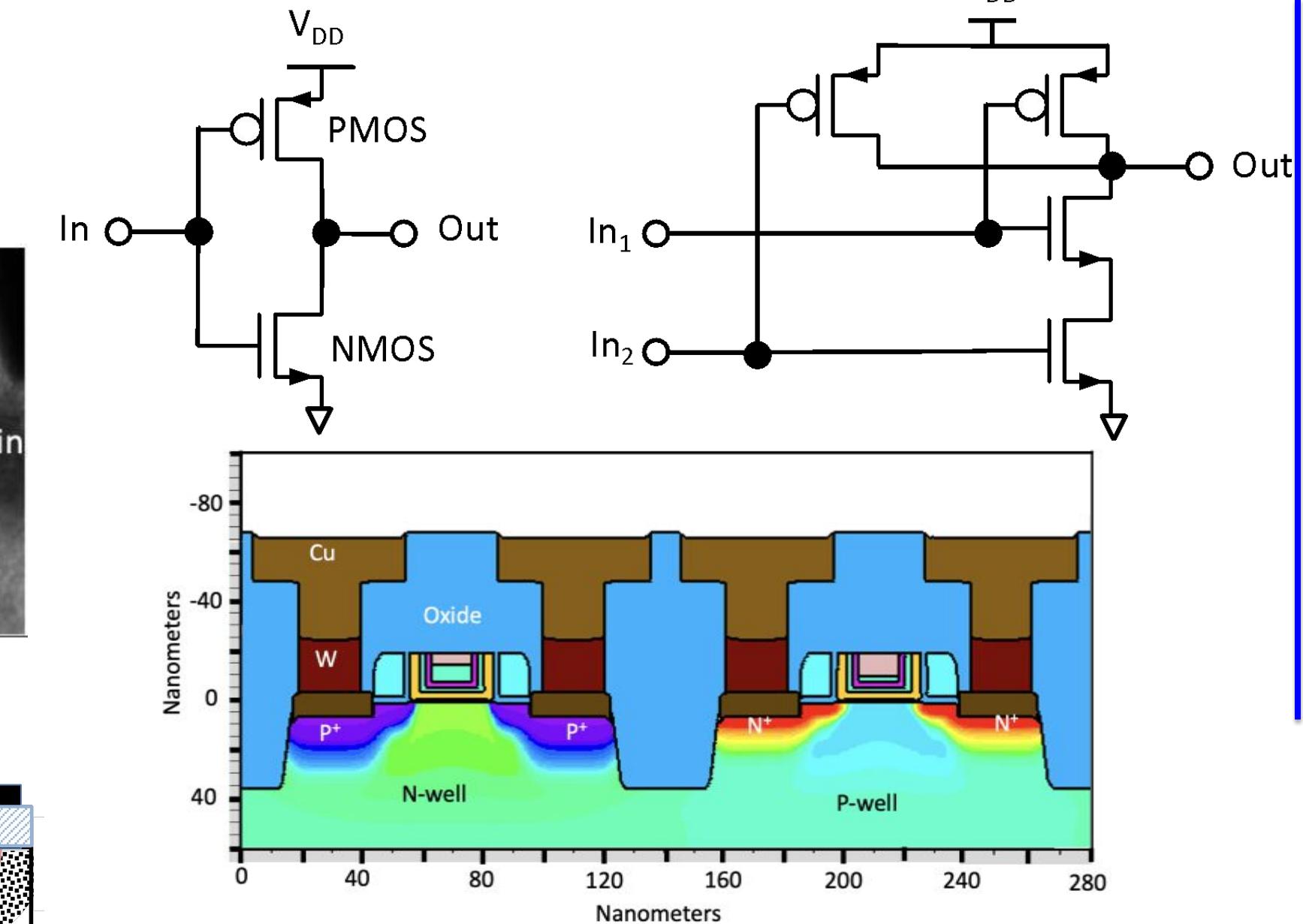
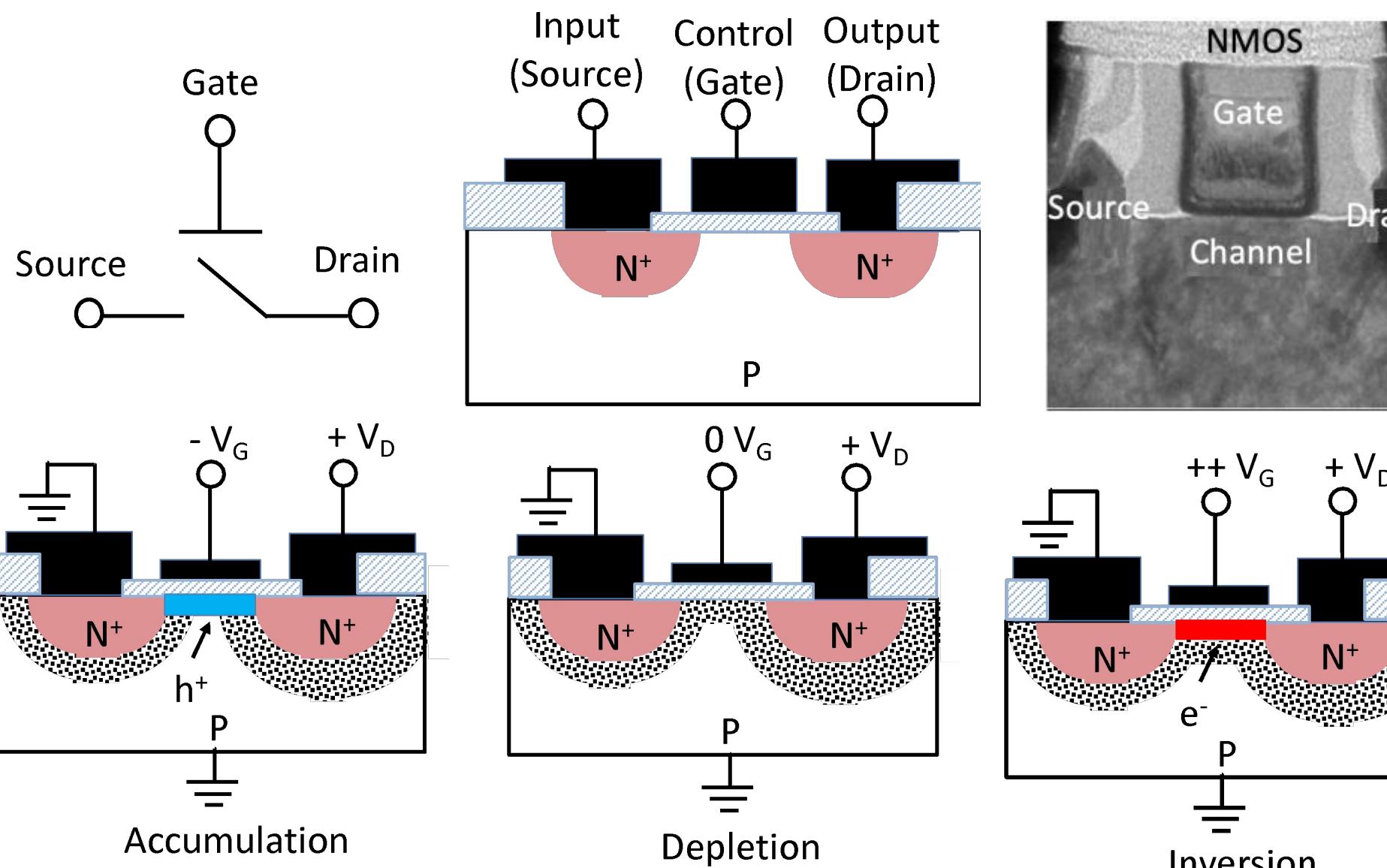


The Sub Micron Transistor



CMOS Transistors with Metal Interconnects

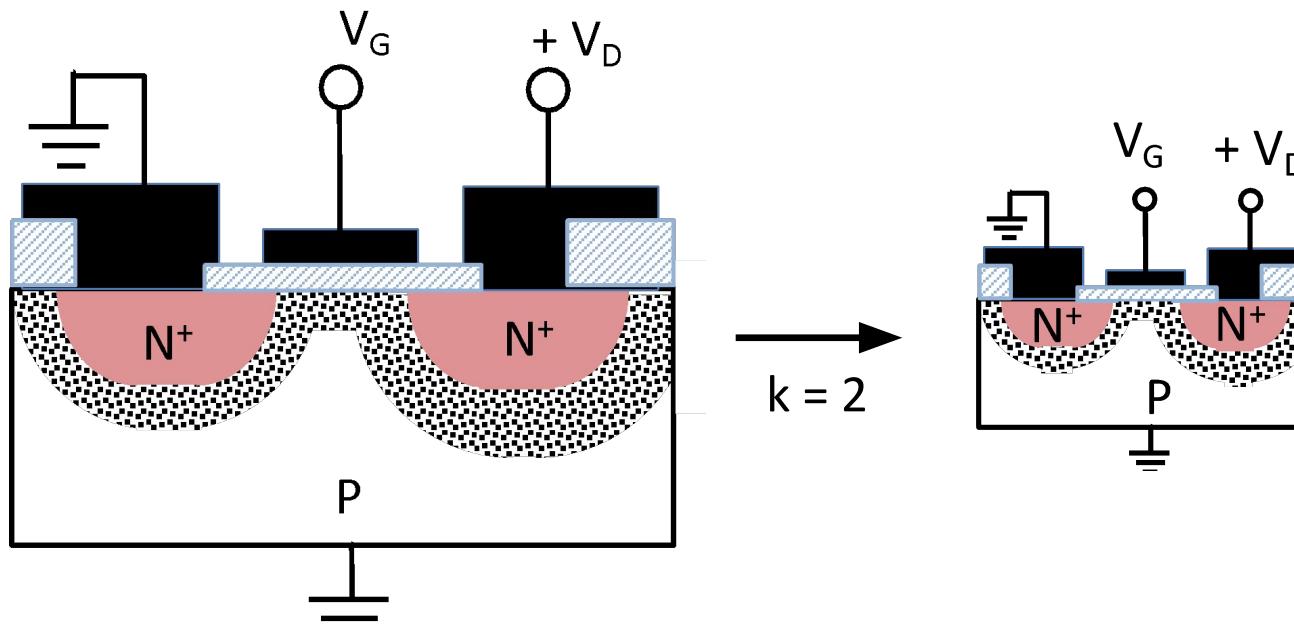
# MOS Vs CMOS



CMOS allows:

- High input impedance.
- 0 DC power dissipation.
- 0 and 1 voltage levels at Gnd and  $V_{DD}$ .
- High  $I_{ON}$ , low  $I_{OFF}$ .
- Highly flexible circuit/system design

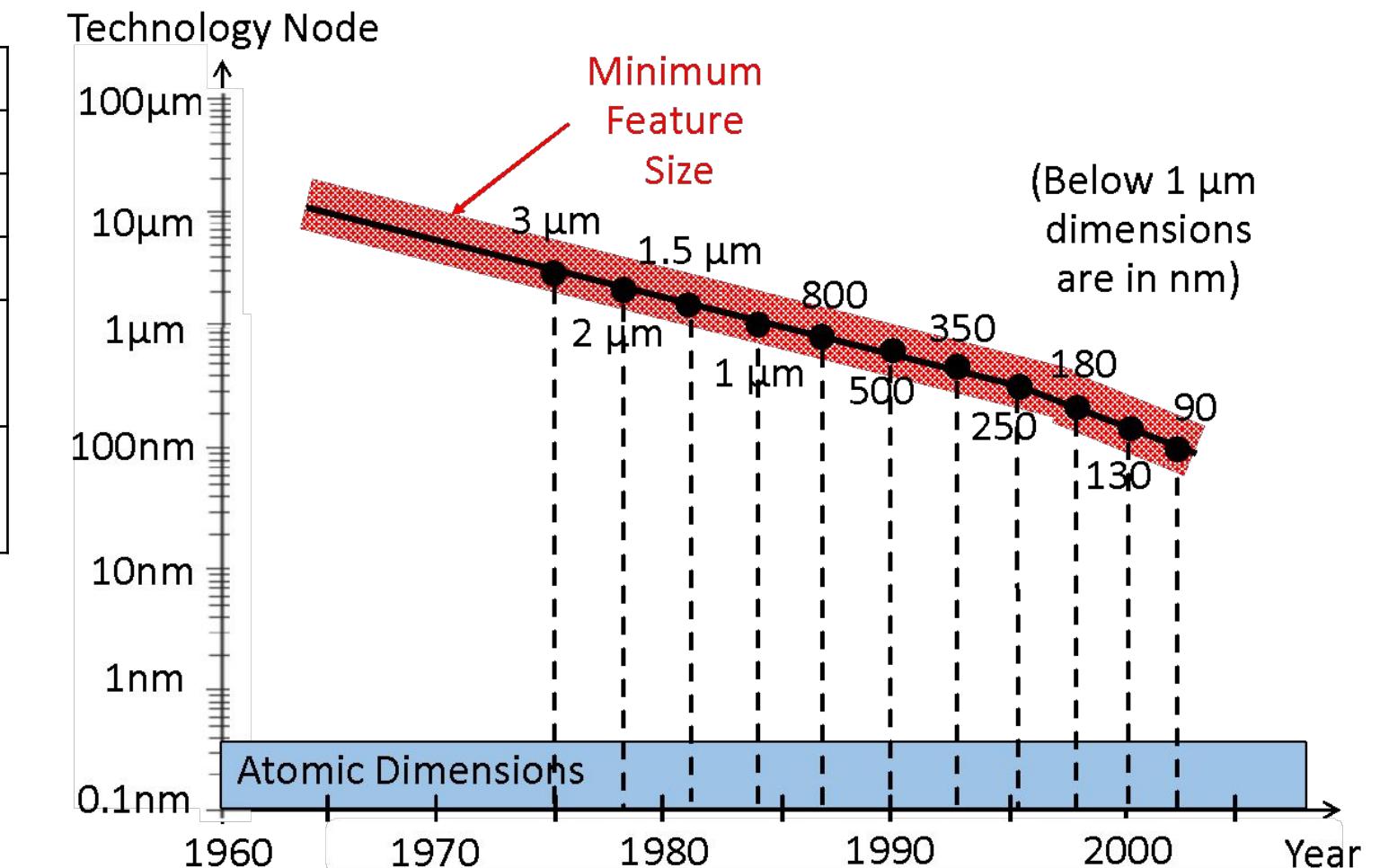
# Dennard Scaling



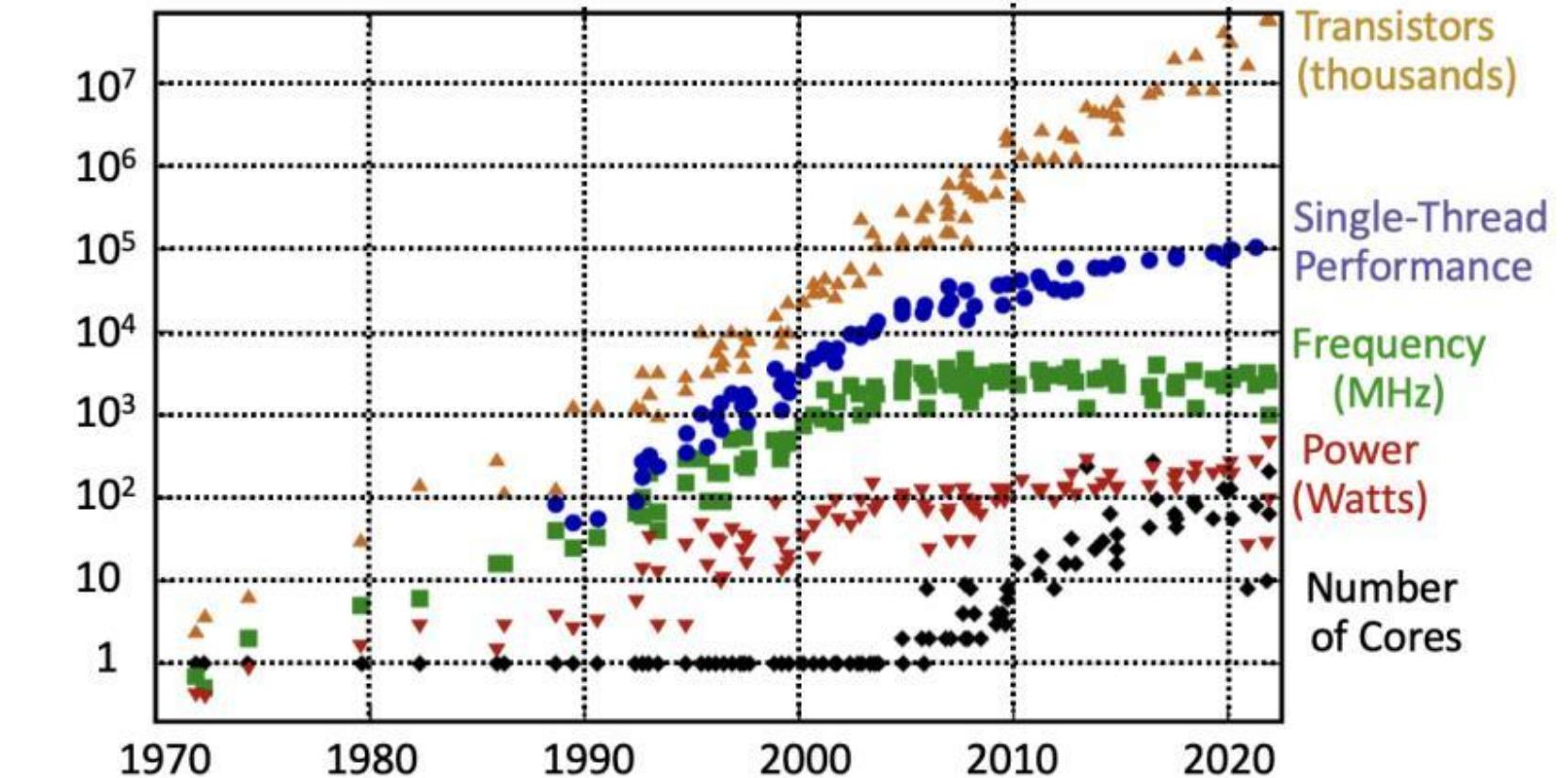
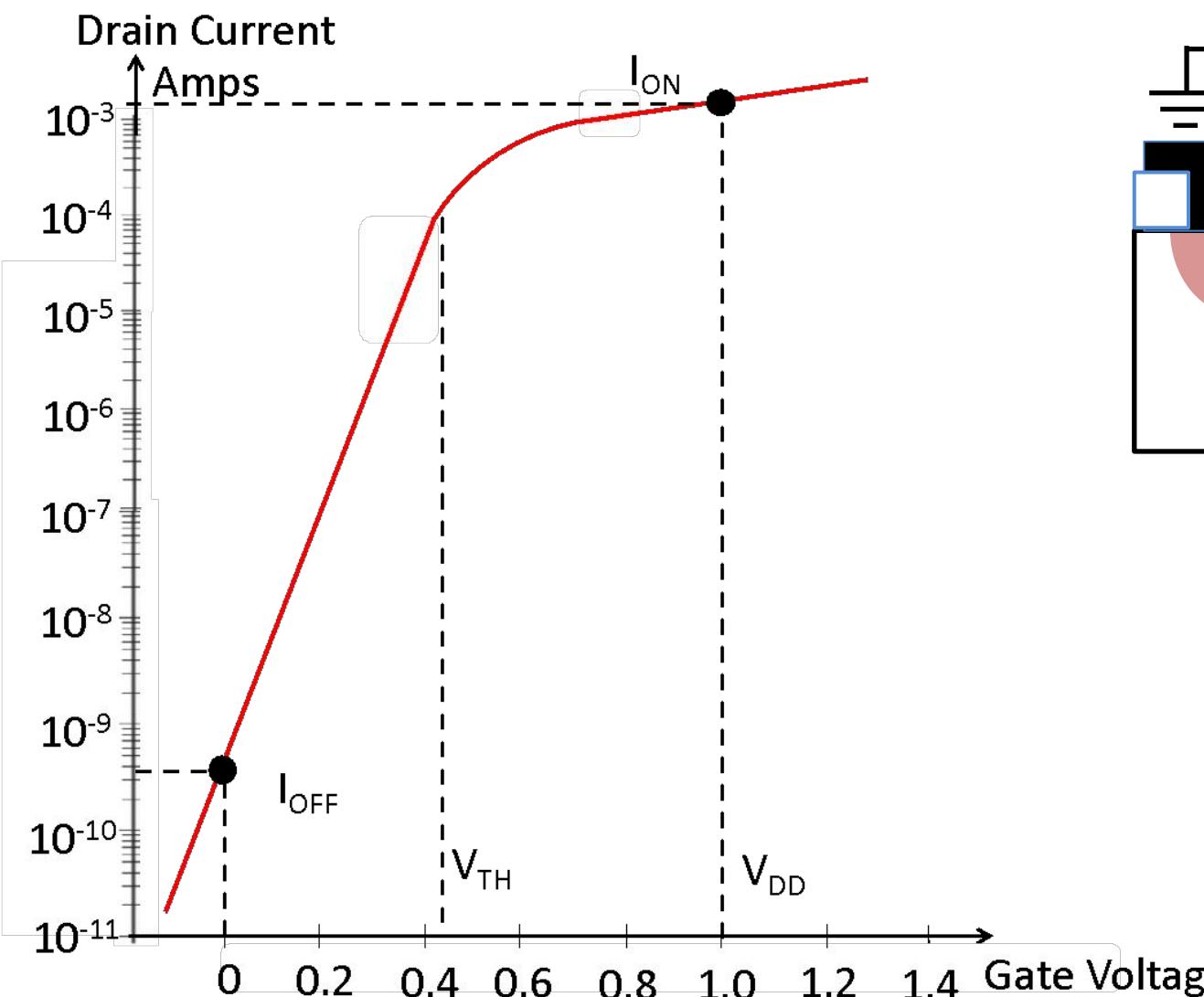
ITRS - 2003 version

Device or Circuit Parameter	Scaling Factor
Device Dimension, $t_{ox}, L, W$	$1/k$
Doping Concentration	$k$
Voltage $V$	$1/k$
Current $I$	$1/k$
Capacitance $\epsilon A/t_{ox}$	$1/k$
Delay time $VC/I$	$1/k$
Power Dissipation $VI$	$1/k^2$
Power Density $VI/WL$	1

Year of Production	2000	2002	2004	2007	2010	2013	2016	2018
Technology Node (nm)	180	130	90	65	45	32	22	14
MPU Gate Length	100	70	53	35	25	18	13	10
DRAM Bits/Chip (GB)	.512	1	4	16	32	64	128	128
MPU Transistors ( $10^6$ )			550	1100	2200	4400	8800	14000
Supply Voltage (V)	1.5-1.8	1.2-1.5	0.9-1.2	0.8-1.1	0.7-1.0	0.6-0.9	0.5-0.8	0.5-0.7

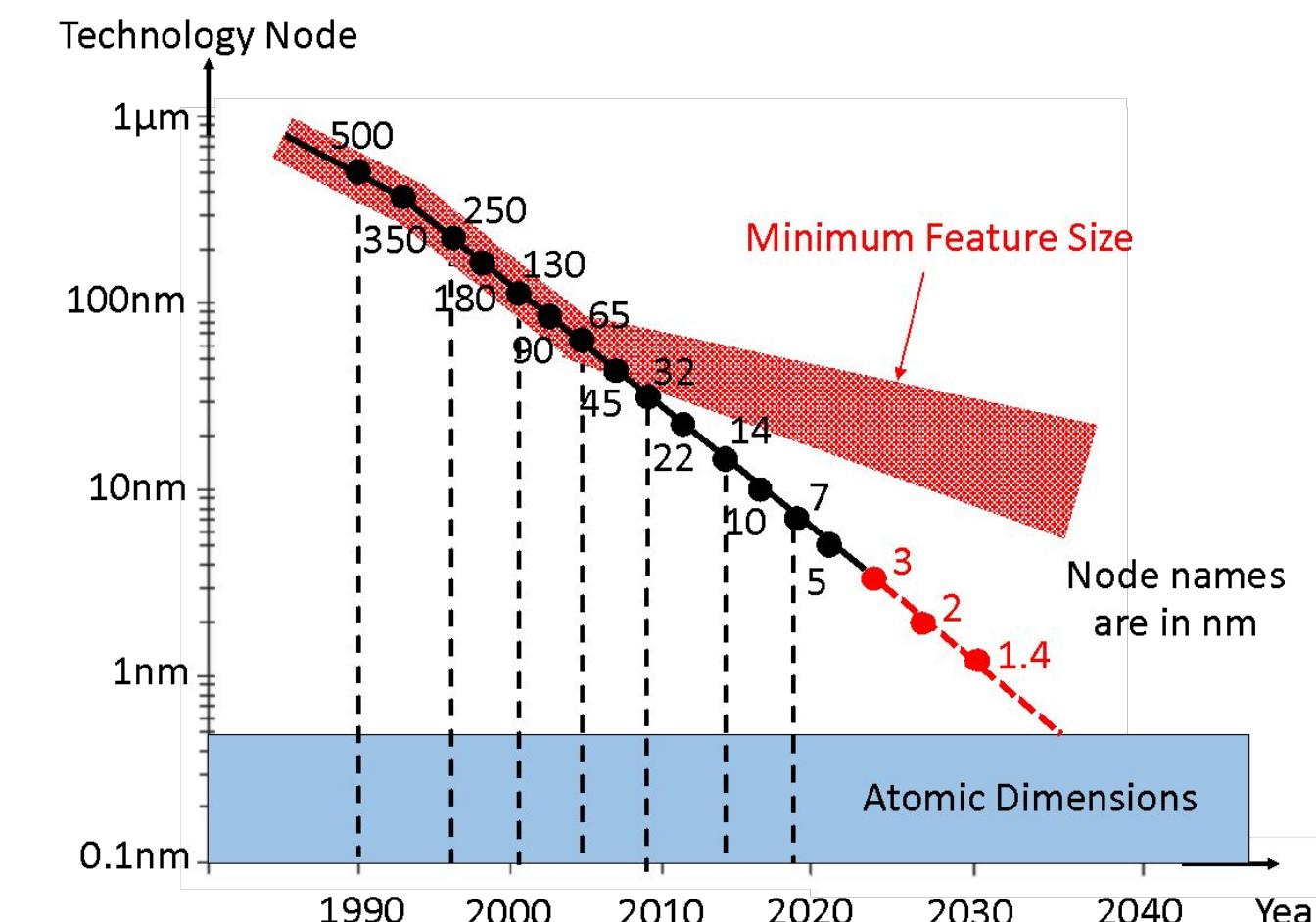
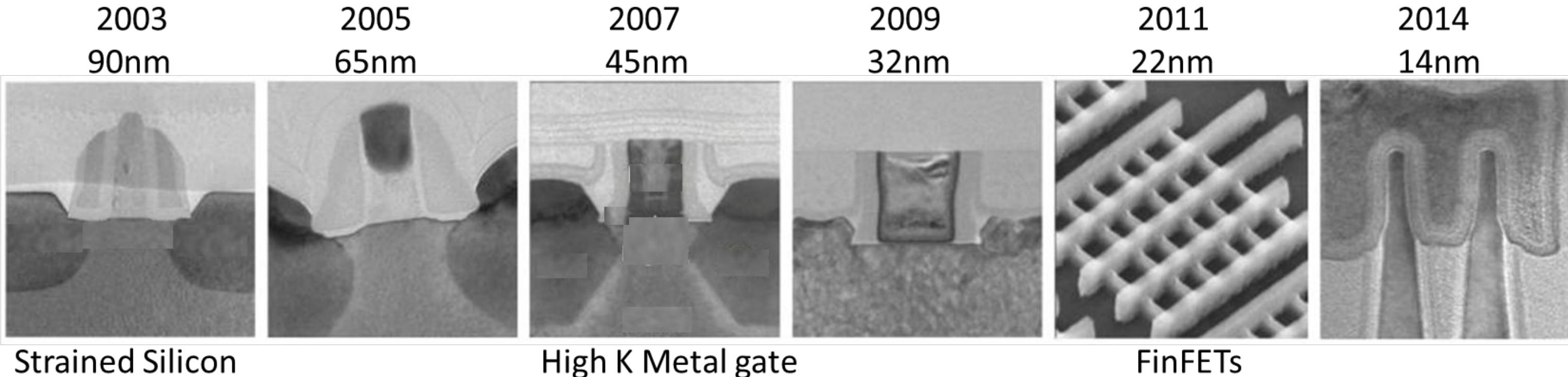


# Non Ideal Scaling

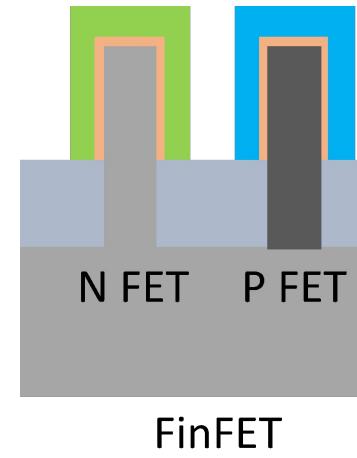


$$\text{Inverse slope} = \frac{kT}{q} \ln(10) = \frac{60\text{mV}}{\text{decade current (I)}}$$

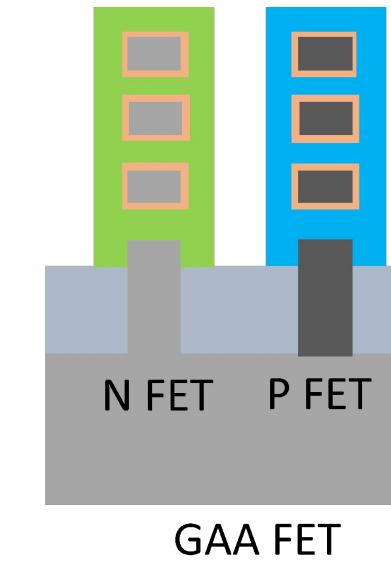
# Beyond Ideal Scaling - Innovations



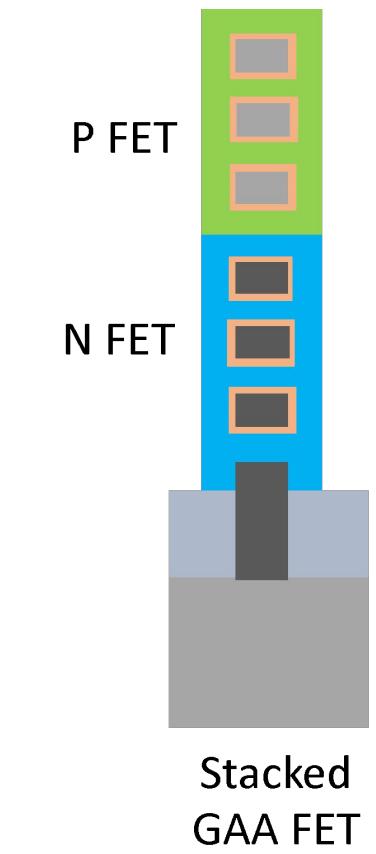
# The two limited Regimes



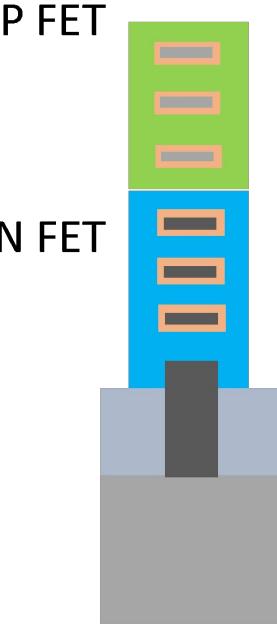
FinFET



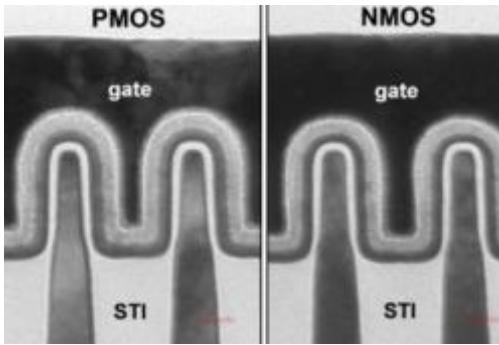
GAA FET



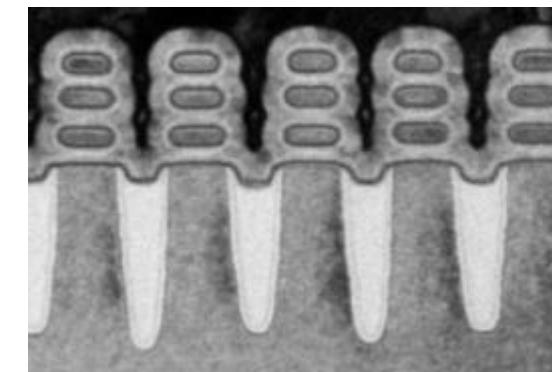
Stacked  
GAA FET



2D Channel  
GAA FET



TSMC



Intel

